



Substitute for form 1448A/PTO

# **INFORMATION DISCLOSURE STATEMENT BY APPLICANT**

Sheet 1 of 1

## **Complete If Known**

Application Number 10/687,288  
 Filing Date October 15, 2003  
 First Named Inventor Wang Yueh  
 Art Unit 1756  
 Examiner Name Daborah Chacko Davis  
 Attorney Docket Number 42P17301

## **NON PATENT LITERATURE DOCUMENTS**

| Examiner Initials* | Cite No.† | Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issu number(s), publisher, city and/or country where published. | T†               |
|--------------------|-----------|--|------------------|
| DCD                |           | LAMMERS, DAVID, "Euro, Japan go to extremes for EUV," EE Times, 10/18/2002, 6 pages  |                  |
| DCD                |           | ITO, H., "Chemical amplification resists: History and development within IBM," <a href="http://researchweb.watson.ibm.com/journal/rd/411/ito.txt">http://researchweb.watson.ibm.com/journal/rd/411/ito.txt</a> , 1997 IBM, 12 pages                            |                  |
| DCD                |           | "Introduction to Electron Beam Lithography," <a href="http://dot.cbe.gatech.edu/henderson/introduction_to_electron_beam_lithography.htm">http://dot.cbe.gatech.edu/henderson/introduction_to_electron_beam_lithography.htm</a> , 13                            | /dcd/ 09/01/2010 |
| DCD                |           | Definition of "PHOTORESIST" from Wikipedia, 2003, one page   |                  |
| DCD                |           | MEDEIROS, D.R., ET AL., "Recent progress in electron-beam resists for advanced mask-making," IBM J. RES. & DEV. vol 45, no. 5, 09/2001, pps. 639-650   |                  |
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| DCD                |           | LINTON, T., ET AL., "Determination of the Line Edge Roughness Specification for 34 nm Devices," TCAD Division, Intel Corporation, 2002 IEEE, pps. 303-306  |                  |
| DCD                |           | STEWART, MICHAEL D., ET AL., "Diffusion Induced Line Edge Roughness," Advances in Resist Technology and Processing XX, Proceedings of SPIE Vol. 5039, 2003, pps. 415-422   | /dcd/ 09/01/2010 |
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Examiner Signature /Daborah Chacko-Davis/ Date Considered 09/21/2006

\*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication.

†Applicant's unique citation designation number. †Applicant is to place a check mark here if English language translation is attached.

Based on PTO/SB/088 (08-03) as modified by Blakey, Schaeff, Taylor & Zafman (w/0) 08/11/2003.  
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